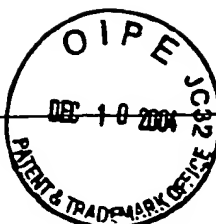


FORM PTO-1449
(REV. 7-80)U.S. DEPARTMENT OF COMMERCE
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510.1015

APPLICATION NO

09/934,723

LIST OF PRIOR ART CITED BY APPLICANT

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APPLICANT

Martin EBINGER

FILING DATE

August 22, 2001

GROUP

2624

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE IF APPROPRIATE
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						
	AJ						
	AK						

FOREIGN PATENT DOCUMENTS

		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUB- CLASS	TRANSLATION	
							YES	NO
	AL	DE 196 000 02	July 11, 1996	DE - Germany			English abstract, Search Report EP 1 202 218	
	AM							
	AN							
	AO							
	AP							

OTHER REFERENCES (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR	D. Sourlier and A. Bucher: Normgerechter Bestfit-Algorithmus fuer Freiformflaechen oder andere nicht-regulaere Ausgleichsflaechen in Parameterform; in: tm- Technisches Messen 59, 1992, 7/8, pages 293 - 302 - includes English abstract, see Search Report of EP 1 202 218
	AS	T. Pfeifer and A. vom Hemdt, Berechnung der Basiselemente und Tasterkompensation in der Koordinatenmesstechnik, Teil 1 Basiselemente; in: tm-Technisches Messen 57, 1990, 3, pages 114-123 - includes English abstract, see Search Report of EP 1 202 218
	AT	H. Weise: Massvergleiche auf Koordinatenmessgeraeten mathematisch auswerten; in: F&M 102, 1994, 9, S.451-454 - includes English abstract, see Search Report of EP 1 202 218
	AU	W. Lotze, Besteinpassung von geometrischen Formelementen und Bohrbildern mit definierten Toleranzonen, in: tm - Technisches Messen 67 (2000) 2, pages 75 - 80 - includes English abstract see Search Report of EP 1 202 218

EXAMINER

WENPENG CHEN
PRIMARY EXAMINER

DATE CONSIDERED

5/2/2005

*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.